

INFORMATION DISCLOSURE CITATION IN AN APPLICATION

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U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
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FOREIGN PATENT DOCUMENTS

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		JP 2000-232057A				Yes	No
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		BURN J. LIN, "The Exposure-Defocus Forest," Jpn. J. Appl. Phys. Vol. 33 (1994) pp 6756-6764
		M. DUSA et al., "Study of mask aerial images to predict CD proximity and line end shortening of resist patterns," Proc. of SPIE Vol. 4349 (2001), pp. 148-159
		B.P. MATHUR et al., "Quantitative Evaluation of Shape of Image on Photoresist of Square Apertures," IEEE Transactions of Electron Devices, Vol. 35, No. 3 (March 1988), pp. 294-297
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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